Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[ThB1] Atomic Scale Etching	
Session Date	November 13 (Thu.), 2025
Session Time	09:00-10:40
Session Room	Room B (Grand Ballroom 1, 2F)
Session Chair	Prof. Thi-Thuy-Nga Nguyen (Nagoya Univ., Japan)

[ThB1-1] [Invited] **09:00-09:30**

Challenges and Approaches of HARC Patterning for AI Memory Devices

Yeonghun Han (SK hynix Inc., Korea)

[ThB1-2] [Invited] **09:30-10:00**

Conversion-Free Atomic Layer Etching (ALE) of ZnO: Effect of Precursor on the ALE Process

Taewook Nam (Sejong Univ., Korea)

[ThB1-3] [Invited] **10:00-10:25**

Ab Initio Analysis of Atomistic Diffusion of Halogen Species at the Etching Front

Sangheon Lee (Ewha Womans Univ., Korea)

[ThB1-4] **10:25-10:40**

Investigation of Wafer Edge Tilting in Capacitively Coupled Plasmas via IEADF-Driven Monte Carlo Feature-Scale Simulation

Sanghyun Jo (Hanyang Univ., Korea), Kyoung-Ho Kim (Korea Polytechnics, Korea), and Ho Jun Kim (Hanyang Univ., Korea)